

Nanonex Delivers Advanced Nanoimprint Tool NX-2000 to Purdue University

Princeton NJ, Mar. 16, 2009: Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the delivery of a Nanonex NX-2000 nanoimprinter tool to Purdue University.

The NX-2000 tool was purchased by Dr. Minghao Qi and Dr. Alexandra Boltasseva from School of Electrical and Computer Engineering. Nanonex is proud to support the cutting edge research of Dr. Qi and Dr. Boltasseva at Purdue University.

The Nanonex NX-2000 is a full wafer nanoimprinter capable of all imprint forms: thermal, photo-curable, and embossing, with sub-10nm resolution. Based on Nanonex's unique patented Air Cushion Press™ technology, the NX-2000 offers unsurpassed uniformity regardless of backside topology, wafer or mask flatness, or backside contamination. This ACP technology also eliminates lateral shifting between the mask and substrate, which significantly increases mask lifetime.

About Nanonex Corporation

Nanonex is the inventor of “nanoimprint lithography”, the world’s first nanoimprint lithography company, and the world’s leading provider of nanoimprint solutions that include equipment, masks, resists and processes. Nanonex’s patented and proprietary nanoimprint lithography (NIL) solutions and Air-Cushion Press™ can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of industry applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of more than 40 tools world-wide. Visit www.nanonex.com for additional information.